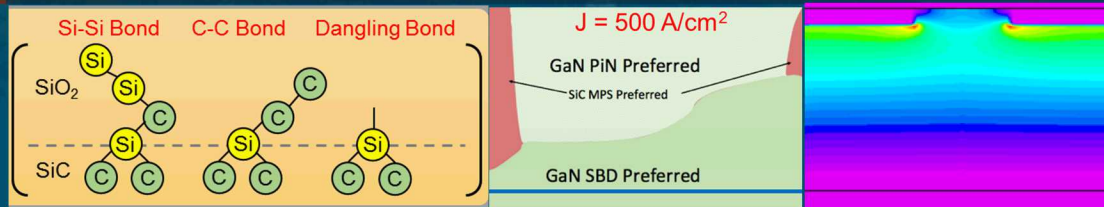
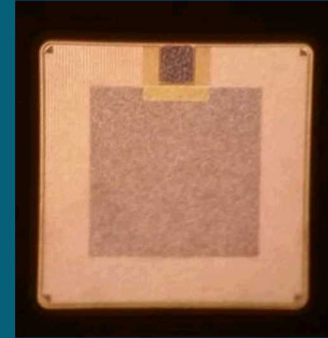


VTO Electric Drivetrain Consortium Keystone #1: Power Electronics Device Research Strategy Overview

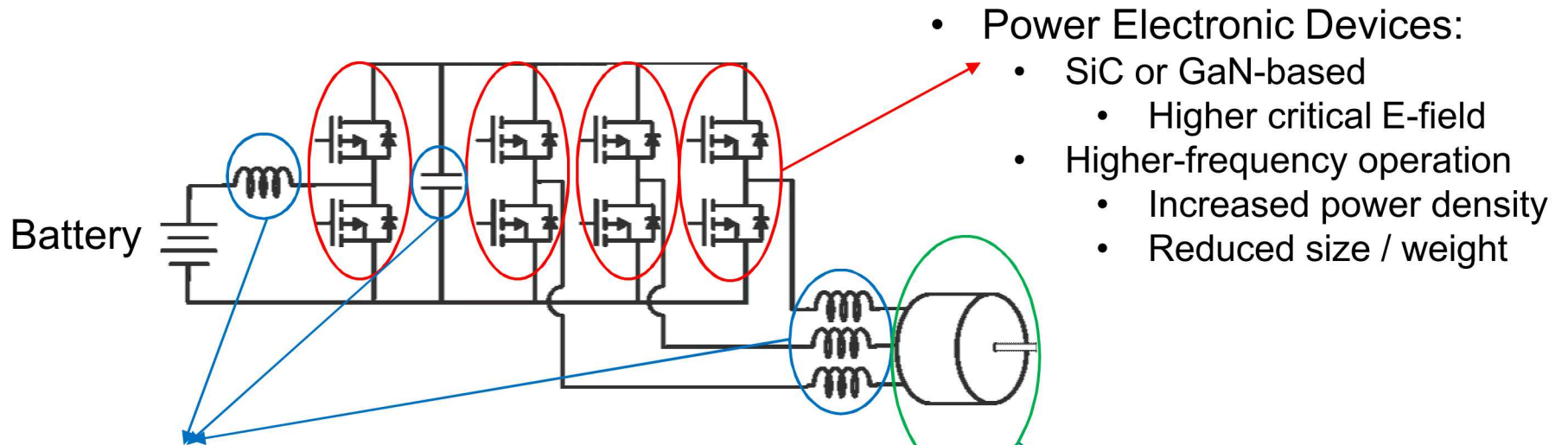


Bob Kaplar
Sandia National Laboratories
June 25, 2019

Objectives

- **Power electronics density target = 100 kW/L**
- **Power target = 100 kW (1.2 kV / 100 A devices)**
- **Cost target = \$6/kW**
- **Operational lifetime target = 300k miles**
- **Barriers:**
 - **Commercial SiC devices may not be designed specifically for automotive environment**
 - **Commercial GaN HEMTs (lateral devices) are typically low-voltage (< 650 V), questions exist concerning reliability (heteroepitaxy)**
 - **Relative immaturity of vertical GaN devices (performance and reliability)**
 - **Relative immaturity of passive materials relative to semiconductors (performance / reliability)**

Approach – System Level View



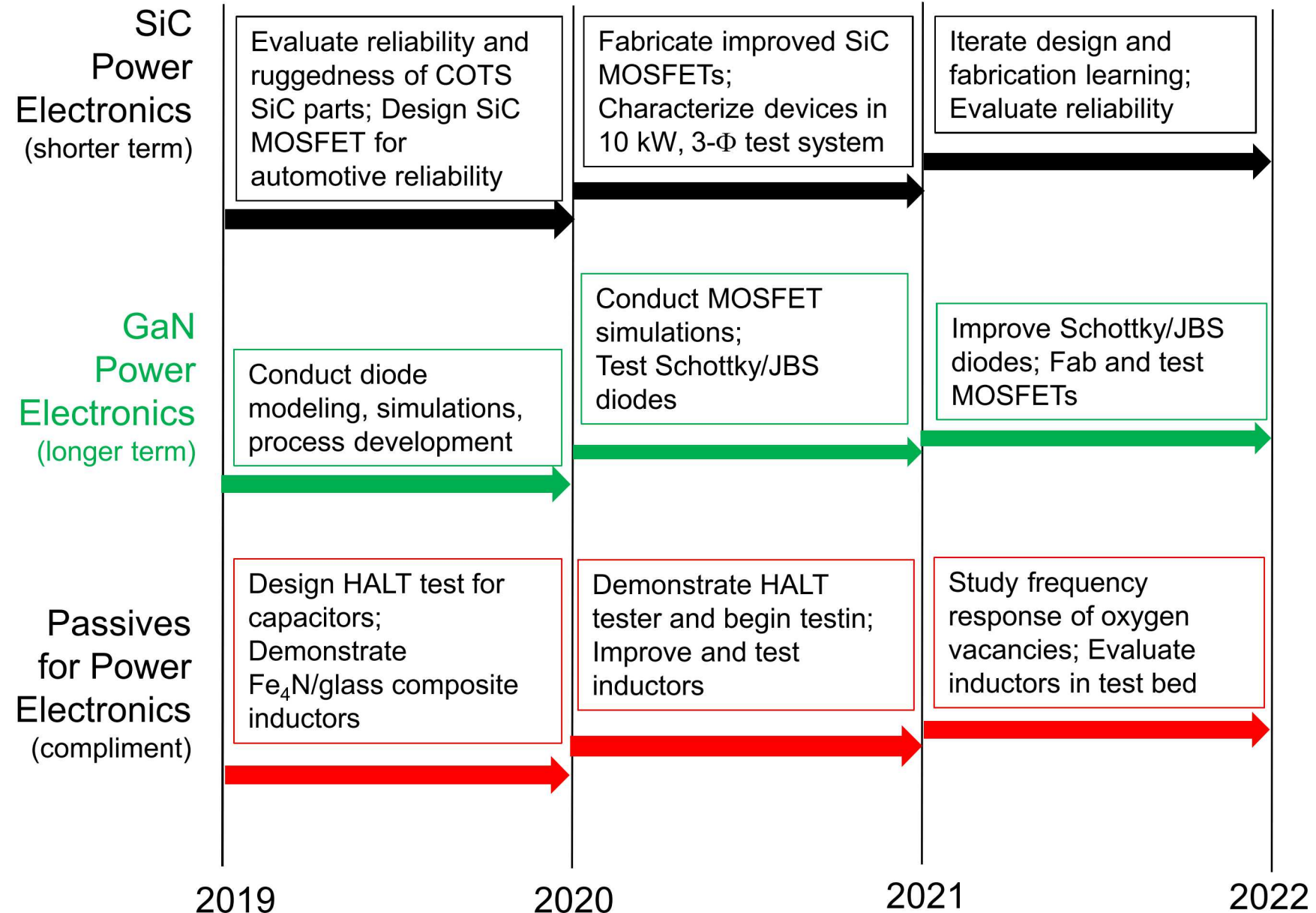
- Power Electronic Devices:
 - SiC or GaN-based
 - Higher critical E-field
 - Higher-frequency operation
 - Increased power density
 - Reduced size / weight

- Passives for Power Electronics
 - Composite materials for improved inductors
 - Improved capacitor lifetime, operating modes
 - Higher-frequency operation
 - Reduced size / weight

- Advanced Motor Designs:
 - Increased power density
 - Higher speed operation
 - Reduced size / weight

- Characterization efforts at each point in the system:
 - Power electronic devices, passives, motors
- Consortium efforts span multiple levels within system design

Approach – Materials for Power Electronics



Consortium Device Team

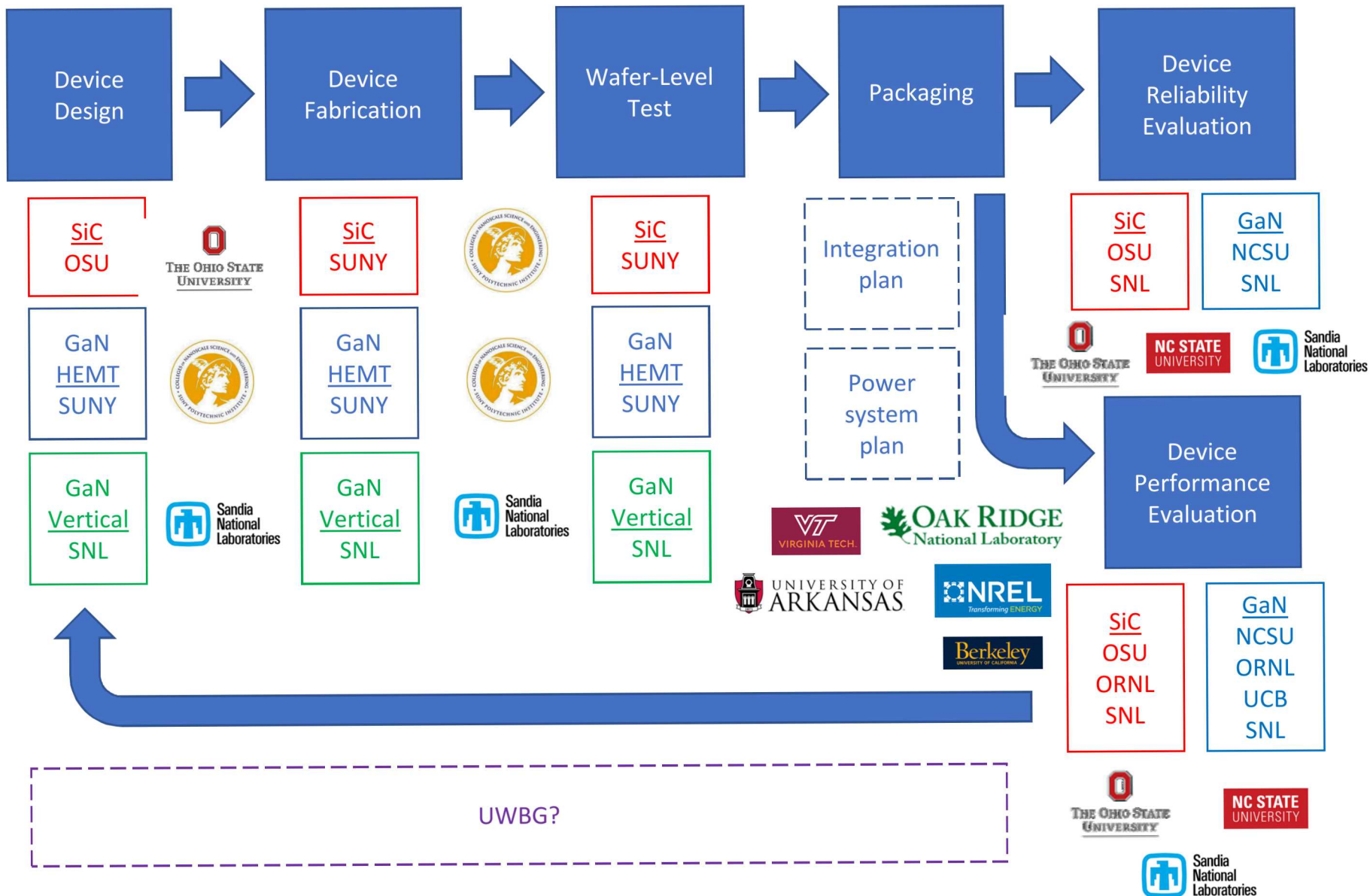
- **Sandia power electronics team**
 - **Vertical GaN devices: Greg Pickrell, Andy Allerman, Mary Crawford, Jeramy Dickerson, Andrew Binder**
 - **Device subcontractors: Jon Wierer (Lehigh), Jim Cooper (Purdue/Sonrisa)**
 - **SiC, power converters, and passives: Jack Flicker, Jason Neely, Lee Rashkin, Todd Monson, Jon Bock**
- **SiC devices (design / fab / test)**
 - **Anant Agarwal (Ohio State), Woongje Sung (SUNY)**
- **Lateral GaN devices**
 - **Shadi Shahedipour-Sandvik (SUNY)**
- **GaN device testing**
 - **Victor Veliadis (NCSU)**



**SUNY Poly
Albany Campus**



Consortium Coordination for Devices



Approach – SiC Power Electronics

- SiC is still young ... but several electric traction drive products have recently featured SiC devices
- Improving the performance of SiC devices is likely to increase its adoption
- Achieve consortium goals within project timeline



PD550 Si IGBT Inverter
9 kW/L

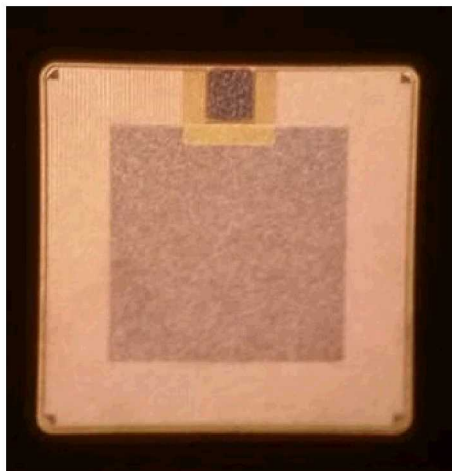


Gen-1 SiC Inverter
18 kW/L
- **Requires 1/3 the space**

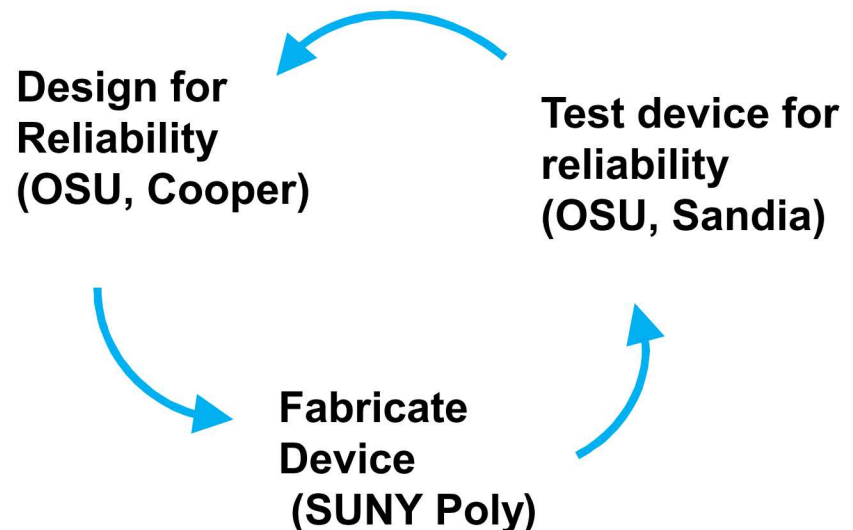
8 SiC Device Strategy

- SiC is one path to Power Electronics target (**shorter term**)
 - SiC has some commercial maturity and a larger manufacturing base
- SiC device designs may not target automotive applications
 - Cost and performance emphasized over reliability
 - High temp. operation causes issues with threshold voltage (< 1 V at 150 C junction temp.)
 - Gate oxides and channel length designs not optimized for automotive environment
- Focus on ***design for reliability*** within cost targets
- Performance and reliability evaluation
 - Characterize new device designs under relevant use scenarios

MOSFET Die

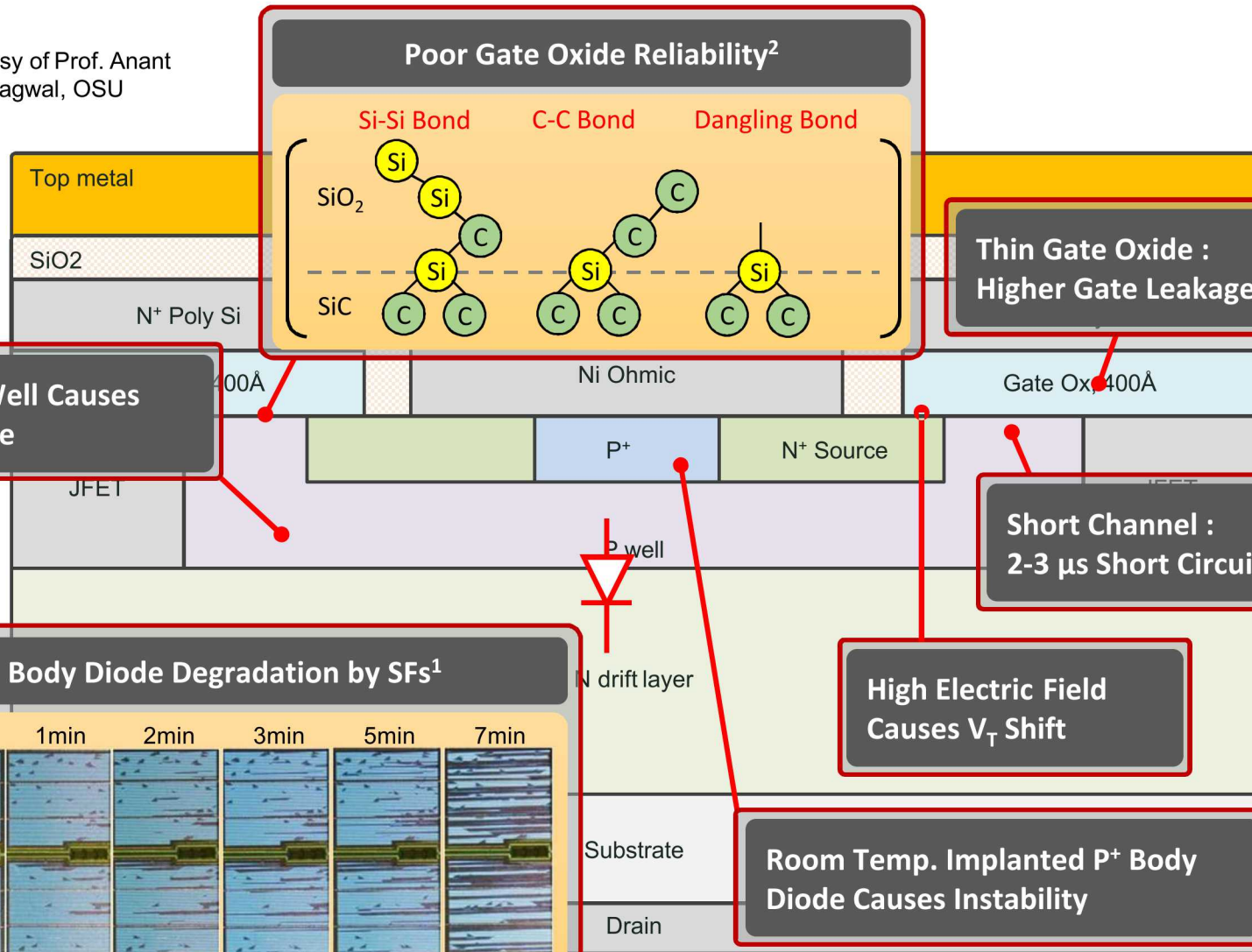


Courtesy of Prof. Woongie Sung, SUNY



SiC Device Reliability – Issues

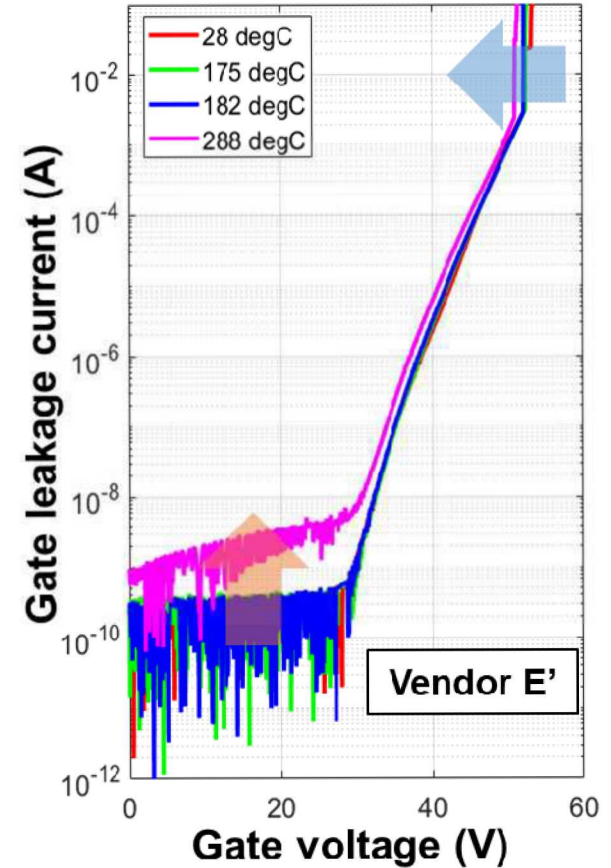
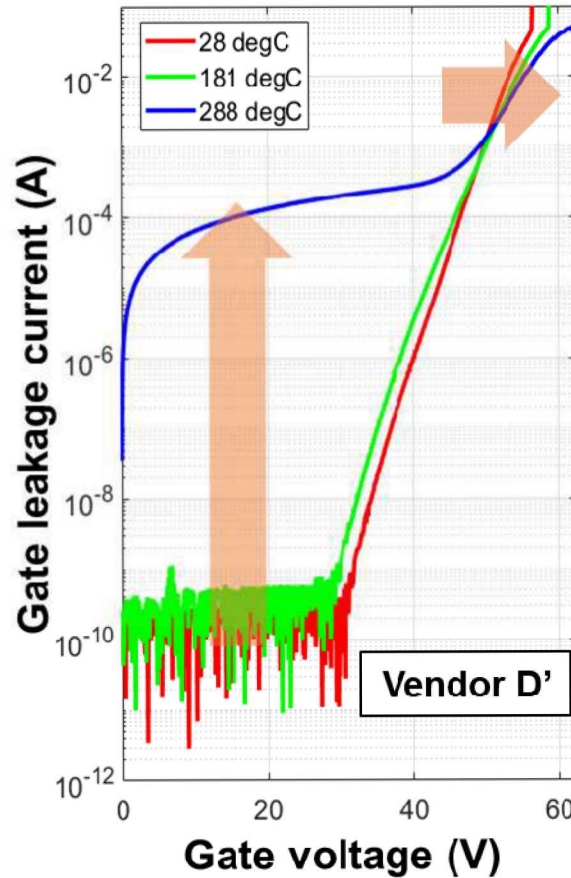
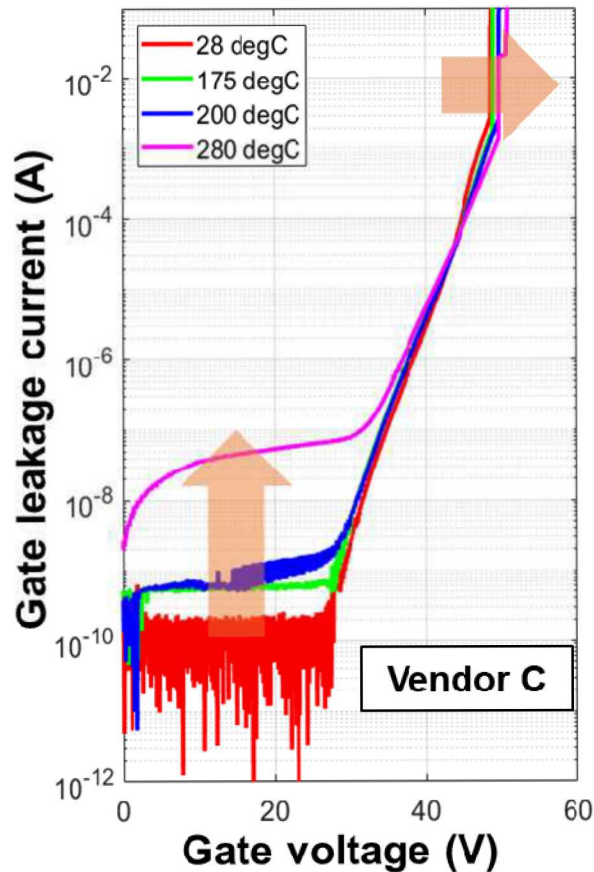
Courtesy of Prof. Anant Aragwal, OSU



¹ Center for Power Electronics Annual Conference 2018, Toyota Motor Corporation

² Courtesy of Prof. Jim Cooper

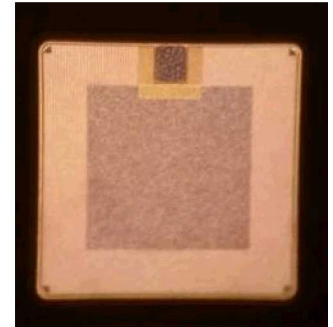
SiC Device Reliability – Gate Current Example



Work in Progress up to 300°C

SiC Cost Targets

- Targets should be achievable by 2023
- Estimates of chip cost for a 1.2 kV / 100 A MOSFET with an integrated JBS diode (chip size 6 × 6 mm²)



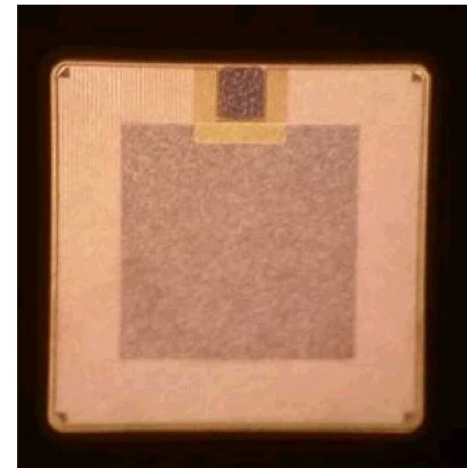
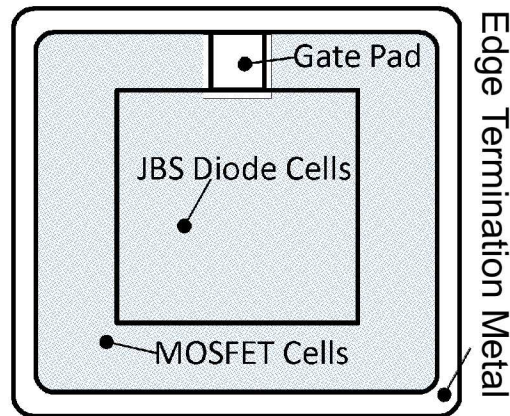
Courtesy of Prof. Woongje Sung., SUNY

	R&D Phase (2018)	Low volume (2020) 10,000 chips per year	Moderate volume (2023) 1 million chips per year	200mm substrate with Moderate volume (2023~)
Cost per Amp	27¢/Amp	10¢/Amp	2.8¢/Amp	1.85¢/Amp
Cost of 150 mm SiC substrate	\$2500	\$1700	\$500	\$750
Process cost per wafer	\$5000	\$1500	\$500	\$500
Cost per 100 A die	\$27	\$10	\$2.8	\$1.85
Total number of chips on a wafer excluding a 2 mm zone around the substrate	400	400	400	750
Yield	70%	80%	90%	90%
Number of functional die per wafer	280	320	360	675

Courtesy of Prof. Anant Agarwal, OSU

SiC Device Fabrication

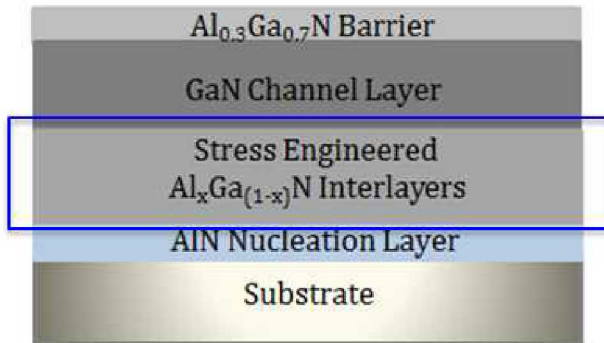
- Reliability/ruggedness evaluation of commercial and SUNY Poly devices
 - Ohio State, Sandia
- Evaluate devices in 10 kW, 3-phase test system
 - Stress devices in realistic drive cycle scenario (e.g. 10 minute hill climb)
- Devices fabricated by SUNY Poly
 - High-performance, high-reliability 900-1700 V SiC JBS diode integrated MOSFETs
 - Devices to be fabricated at a commercial foundry



Courtesy of Prof. Woongie Sung, SUNY

Lateral GaN Power Devices

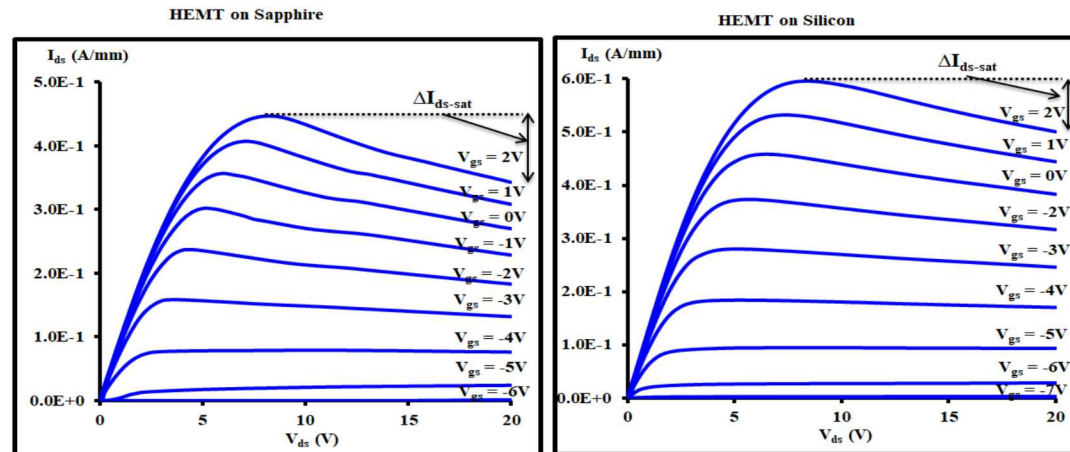
- AlGaIn/GaN HEMT is the most mature GaN power device, but continues to suffer from less-than-ideal reliability due mainly to growth on foreign substrates (e.g. SiC, Si, Sapphire)
- Consortium work will focus on growth and fabrication of AlGaIn/GaN HEMTs on native GaN substrates



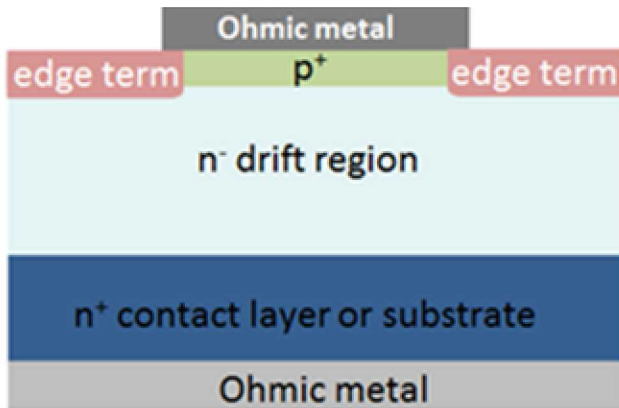
- Eliminate strain engineered layers by growing on native GaN substrates
 - Lower defect density is expected to lead to better device performance and reliability



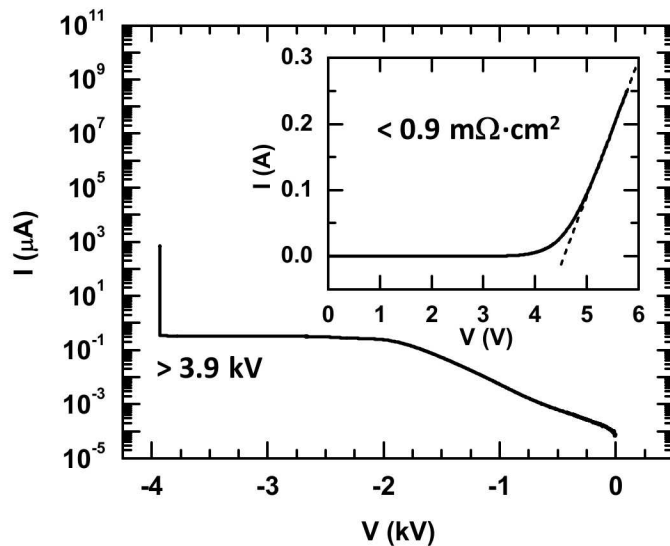
Courtesy of Prof. Shadi Shahedipour-Sandvik, SUNY



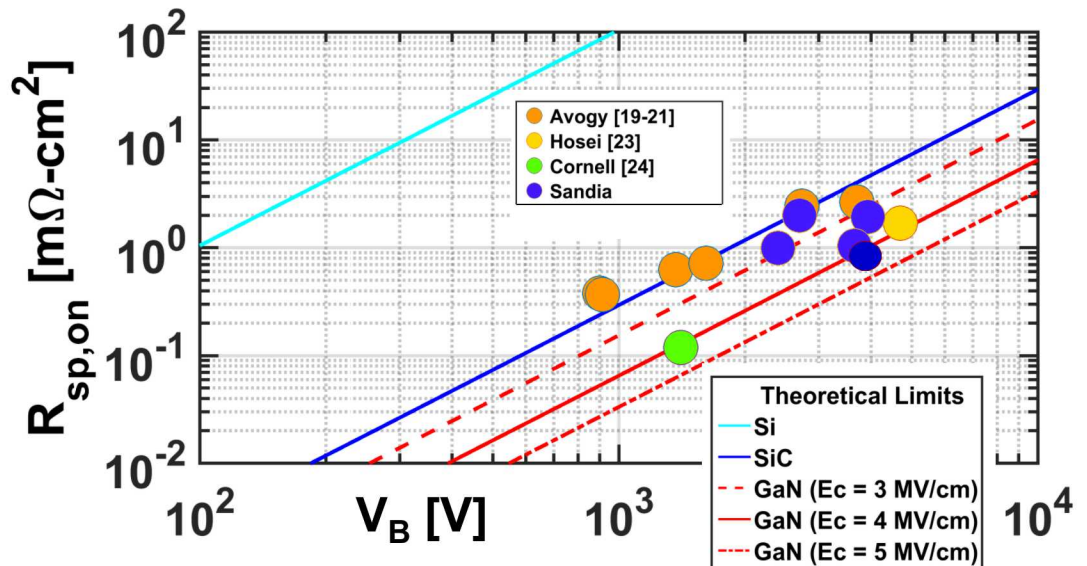
Vertical GaN Power Devices



- Vertical device architecture enables higher breakdown voltages
 - Similar to Si and SiC power devices
 - Better performance due to higher critical electric field for GaN
- Less mature – Challenges exist with substrates, growth, and processing

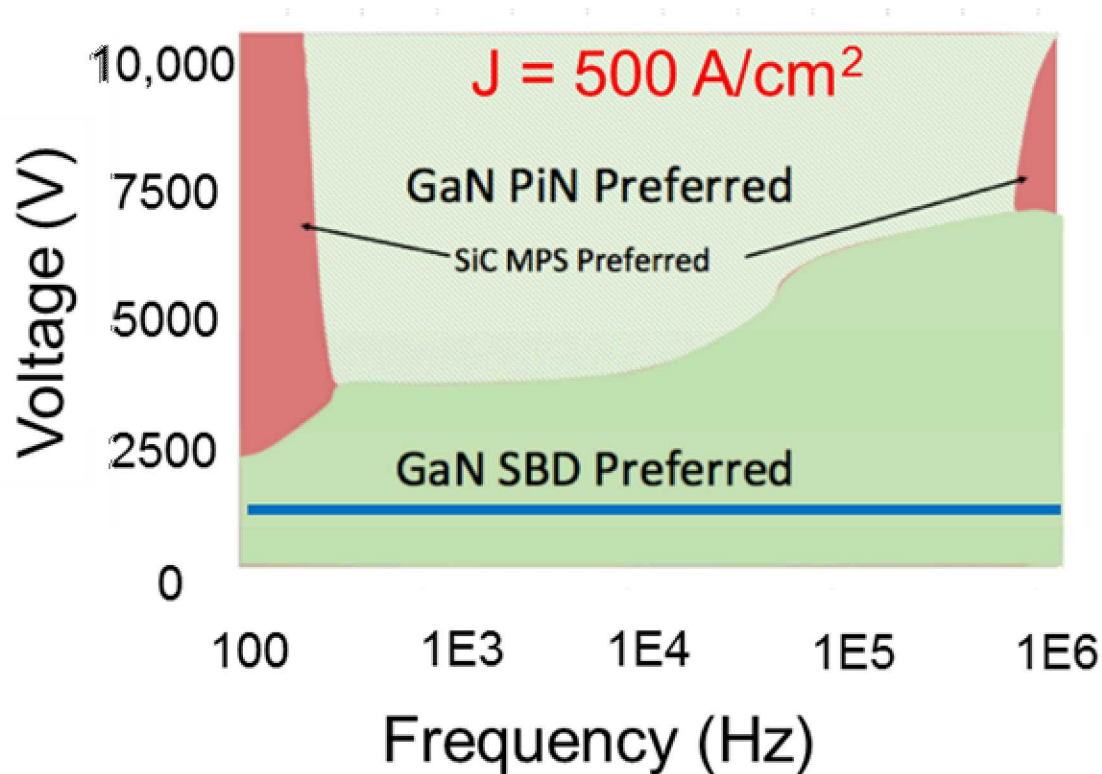


A. Armstrong et al., Elec. Lett. 52(13), 1170 (2016)



System Benefits for Vertical GaN

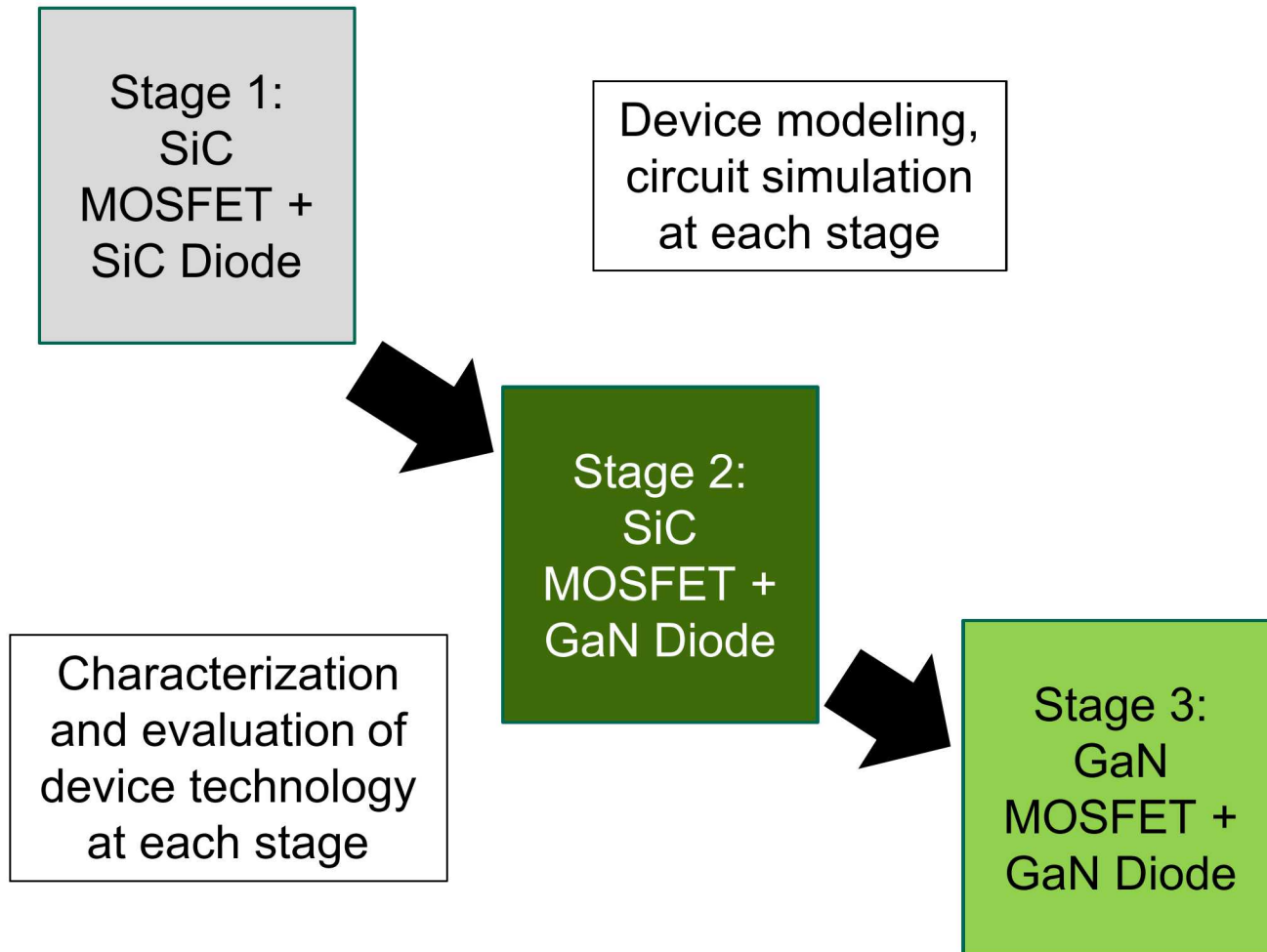
System evaluation of **diode power dissipation vs. diode type**
for given operating regime (reverse voltage, forward current density, frequency), $T = 300\text{ K}$



- Lower R_{on} for GaN SBD and JBS diodes drive expected performance benefits
- Target operating voltage for EDT power devices: 1200 V (blue line)

Evolution of Vertical GaN Devices

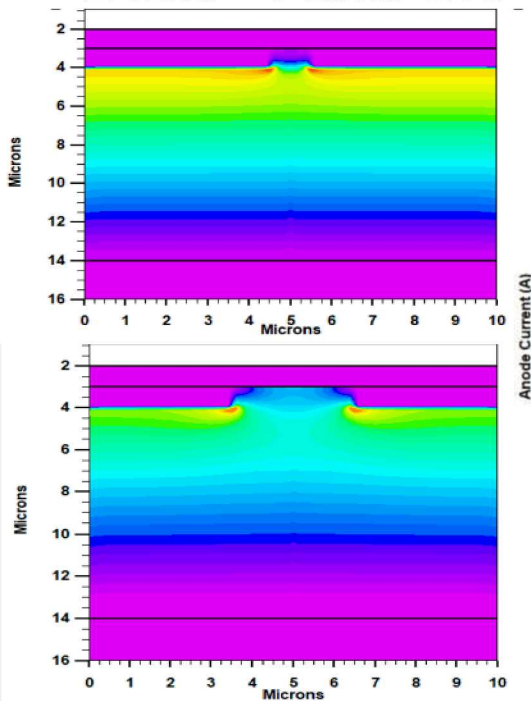
Follow successful commercial model of **staged** device integration from Si + SiC development



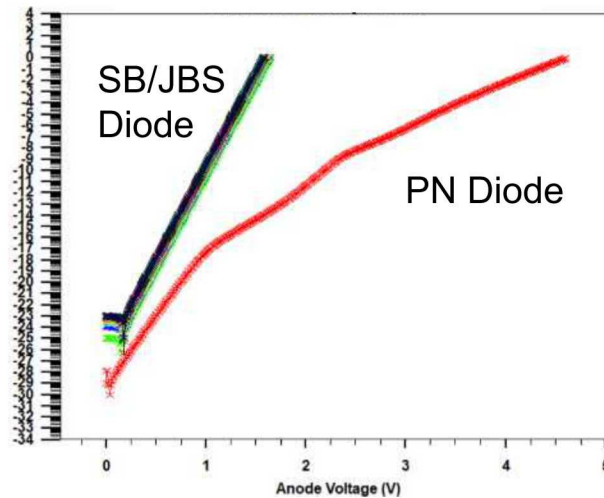
Progress on GaN Vertical Devices

- Decision to focus resources in first year on the vertical GaN diode
 - Allows staged combination with SiC transistors.
 - Schottky Barrier (SB) and Junction Barrier Schottky (JBS) diodes
- Modeling/Simulation is underway
 - Have developed SB diode models in Silvaco simulation software
 - JBS diode models are under development

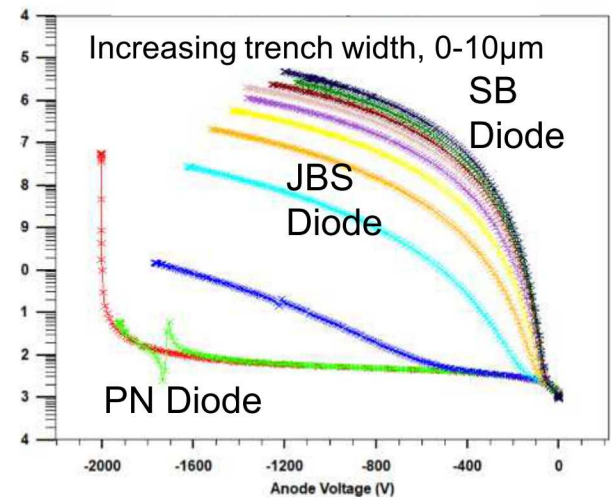
E-field – Planar JBS



JBS - Forward IV



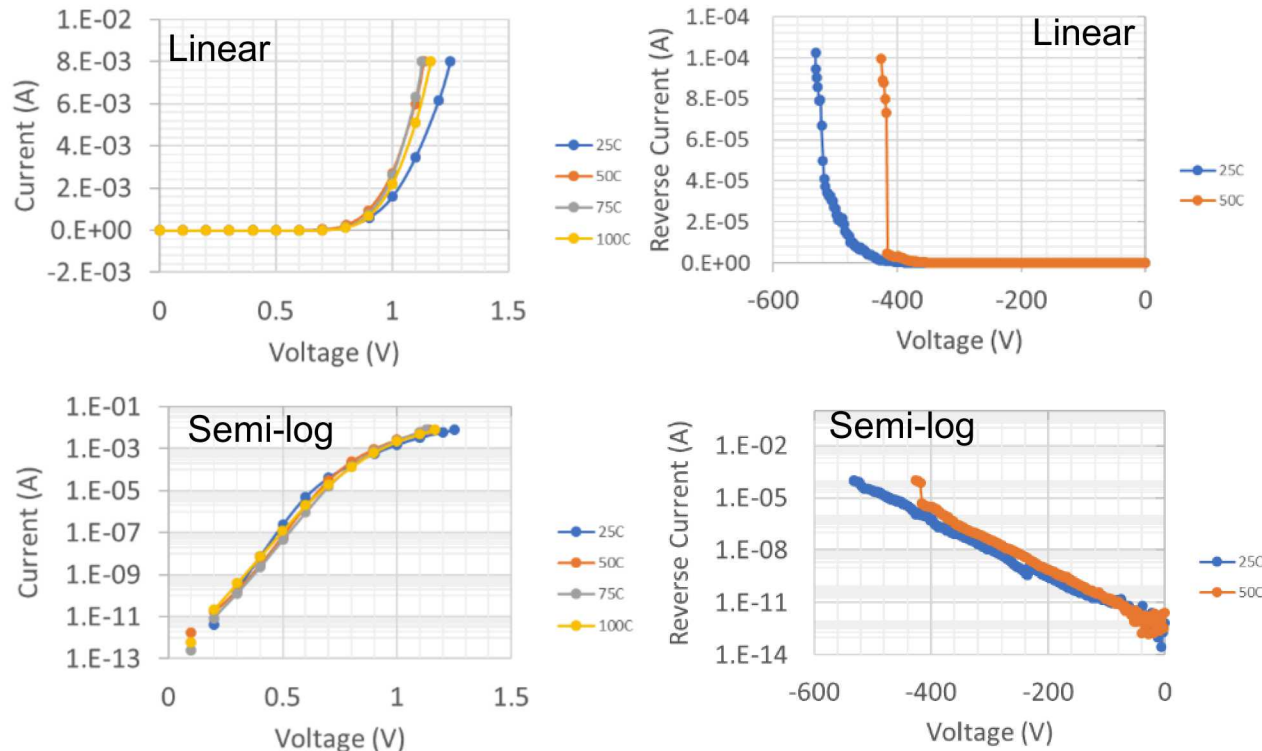
JBS - Reverse IV



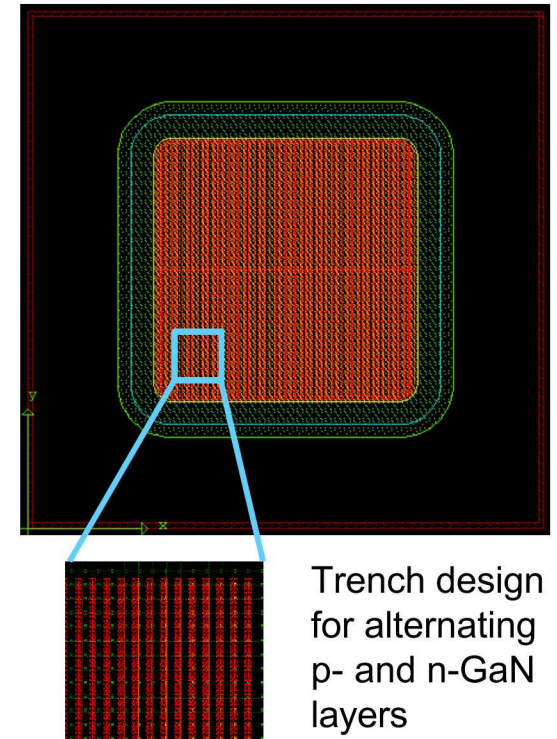
Progress on GaN Vertical Devices

- Gen1 GaN SB Diodes **demonstrated**
 - SB diodes are being characterized and used to calibrate models
 - Focus on good Semiconductor-Metal interface for Gen1 devices
- Mask designs for JBS diode development **completed**
 - Exploring different design strategies
 - Using SiC devices to understand current scaling methods

SB Diode IV over Temperature

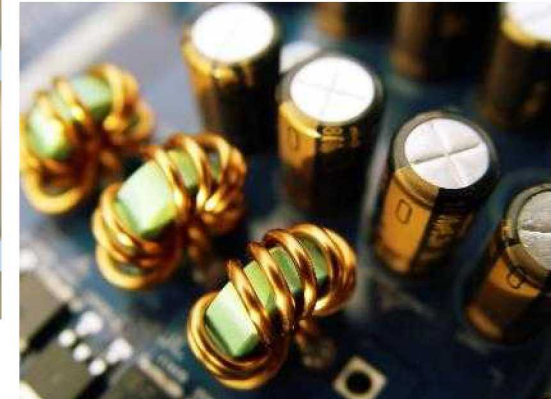
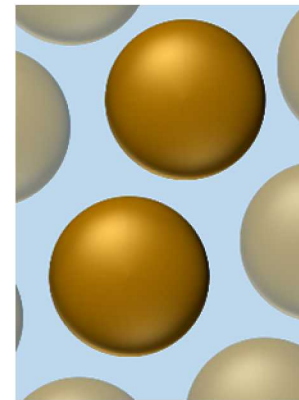
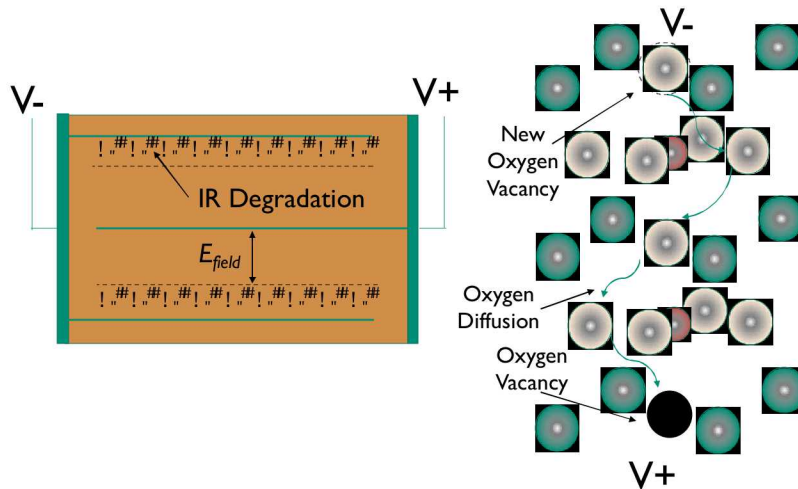


JBS Diode Mask



Passive Materials for WBG Power Electronics

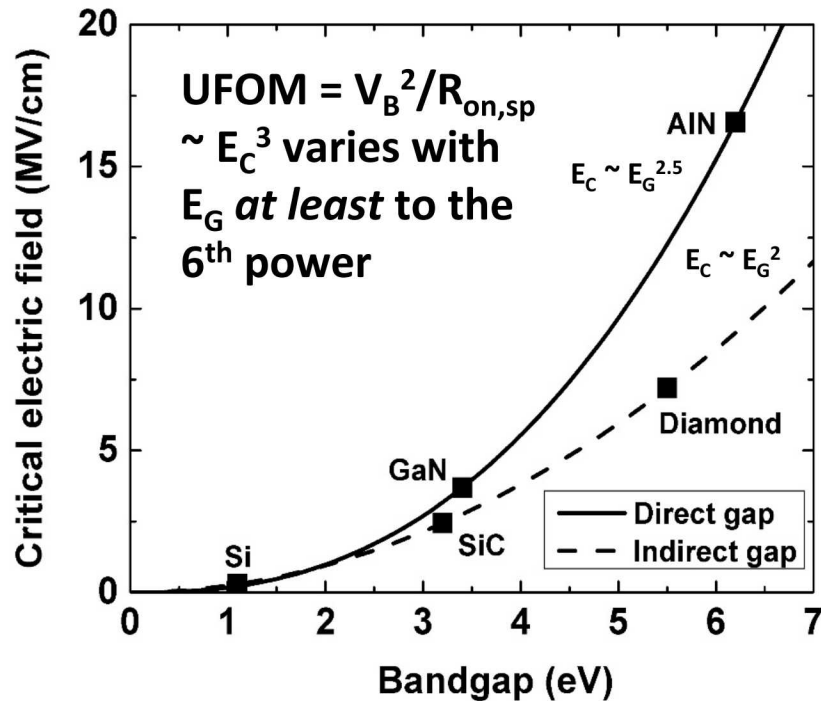
- Innovate passive materials for high-frequency power electronics
 - Improve ceramic capacitor performance and reliability
 - Increase frequency of magnetic materials and reduce size of inductors
 - Increase power density through integration (vs. discrete components)



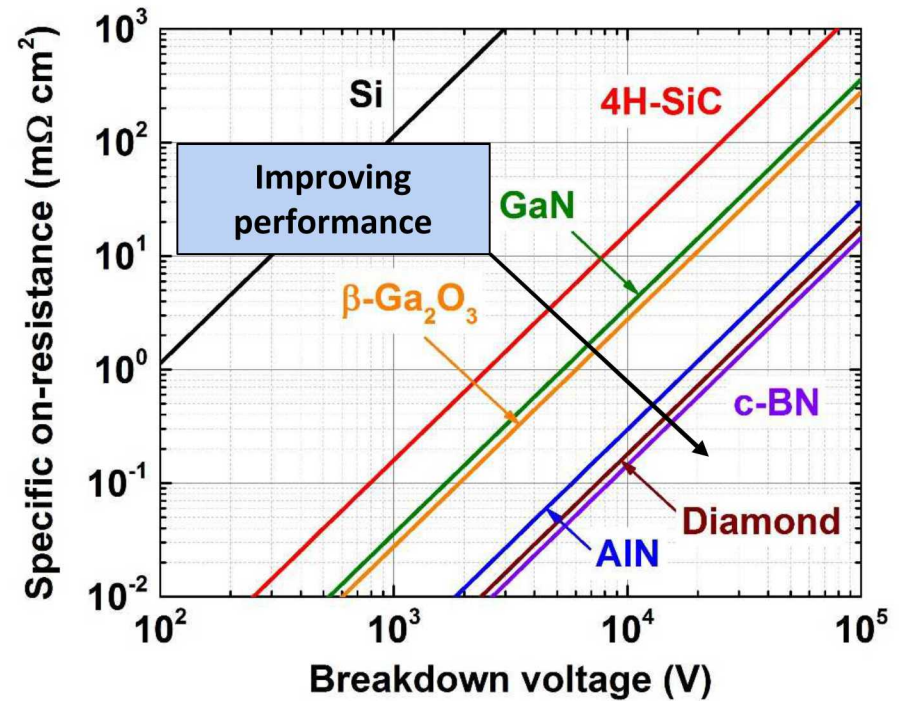
With permission from Getty Images

- **Ceramic capacitor aging caused by oxygen diffusion toward anode and accumulation of oxygen vacancies at cathode**
- **Bipolar switching at $\sim 10\times$ the rated voltage and 125°C above the rated temperature can increase the lifetime**
- **Inductor designs may be improved with tailored Fe_4N composites**
 - **Smaller size**
 - **Higher-frequency operation**
 - **Operating temperatures up to 200°C**

Future Work: UWBGs?



Strong dependence of E_c on E_g leads to better performance



Unipolar FOM =

$$V_B^2 / R_{on,sp} = \epsilon \mu_n E_c^3 / 4$$

Summary

- **Systems-level view has identified key areas to focus on for device development**
 - **Wide-bandgap power devices – SiC and vertical GaN devices are main efforts, with some work on lateral GaN**
 - **Close coordination between Sandia, other DOE labs, and key universities**
- **SiC device improvement will be driven through “design for reliability” approach with performance metrics and cost in mind**
 - **Iterative cycles of design, fab, and performance and reliability evaluation across partner institutions**
- **GaN device development is underway**
 - **System-level benefits being evaluated**
 - **HEMT effort focused on reliability**
 - **Vertical GaN Schottky and JBS diode work is in progress**
 - **Vertical GaN MOSFET work starting**
- **Suitable passive components are required to take full advantage of WBGs**